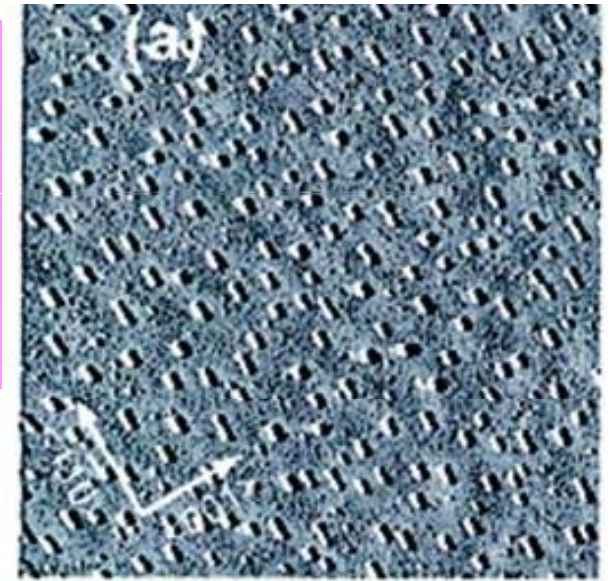
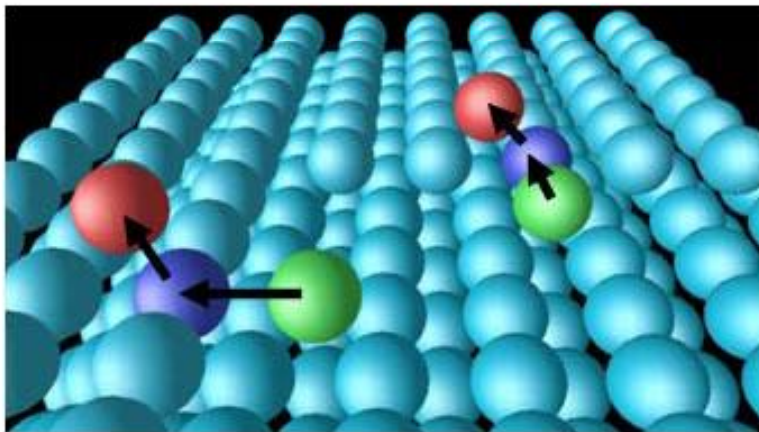
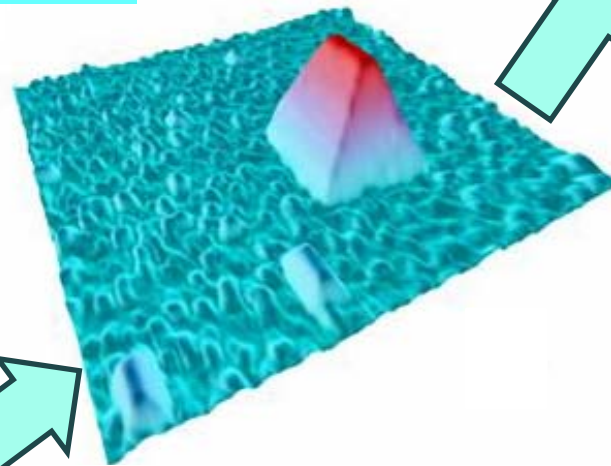


# Multi-Scale Simulation of Assembly at Gas-Solid Interfaces: Al/Al(110)



Kristen A. Fichthorn  
Penn State University

Sponsored by  
NSF DMR-0514336



Yogesh Tiwary's  
PhD

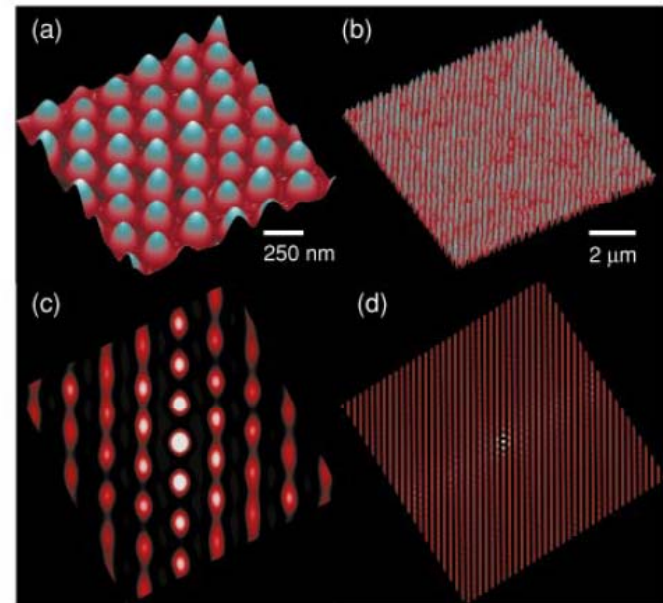
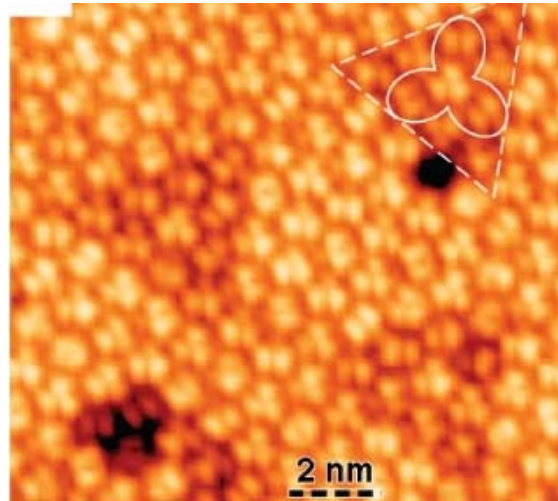
# Patterned Substrates Are Useful!

## Templates for Molecular Assembly

C60 on Ag/Pt(111)

K. Ait-Mansour et al.,  
J. Phys. Chem. C  
**113**, 5292 (2009).

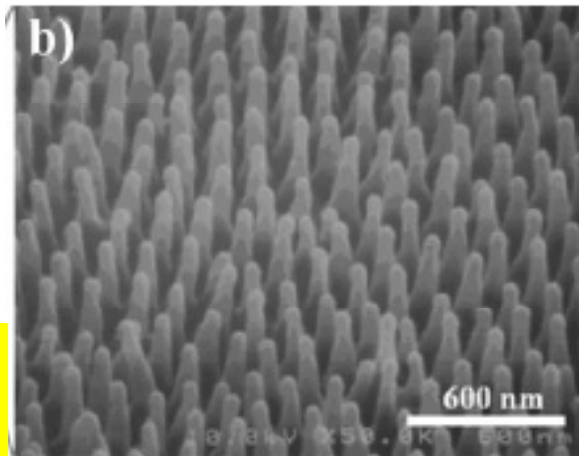
J. Howe, ..., K. Fichtorn,  
*PRB* **81**, 121410 (2010).



## Superhydrophobic Properties

Cicada Wing

W. Lee et al., Langmuir **20**, 7665 (2004).



H. Wu, ..., K. F.  
*J. Chem. Phys.* **133**  
054704 (2010).

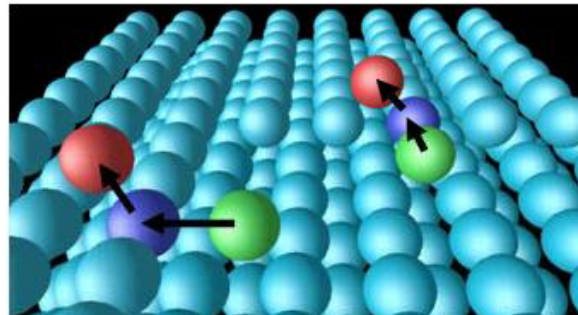
## Optoelectronic Properties

Ge/Si(001) Quantum Dots

O.G. Schmidt et al., Appl. Phys. Lett.  
**77**, 4139 (2000).

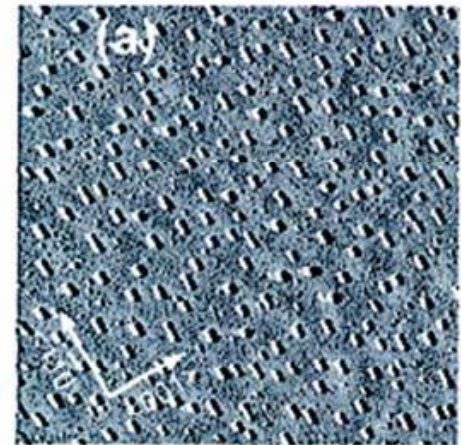
We want to Design  
Their Assembly From  
the Bottom Up!

# Hut Formation in Al(110) Homoepitaxy

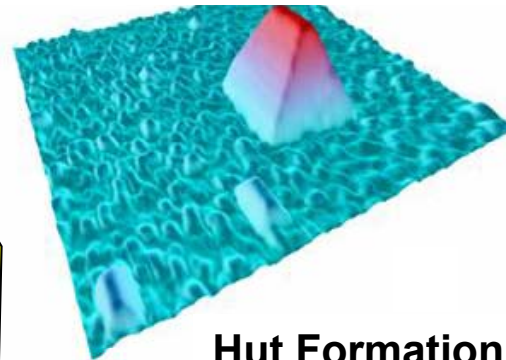


Atoms Hopping ( $\text{\AA}$ , ps)

Bautier de Mongeot *et al.*, *Phys. Rev. Lett.* **91**, 016102 (2003).



Hut Organization ( $\mu\text{m}$ , min)



Hut Formation (nm, min)

Zhu *et al.*, *Phys. Rev. Lett.* **92**, 106102 (2004).

## Multi-Scale Kinetic Self-Assembly

K. Fichthorn and M. Scheffler, *Nature* **429**, 617 (2004).

# Describing Multi-Scale Self-Assembly in Al(110) Homoepitaxy

## First-Principles DFT

VASP Code

Diffusion Barriers

Adatom Interactions

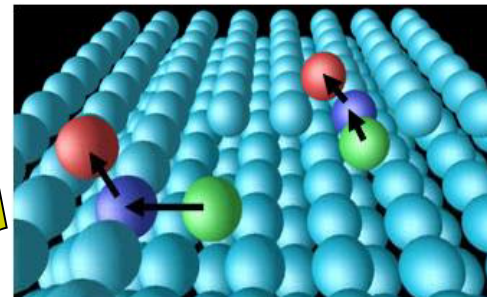
Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **75**, 235451 (2007);  
*Phys. Rev. B* **78**, 205818 (2008);  
*Phys. Rev. B* **81**, 195421 (2010);  
*Phys. Rev. B* (submitted).

## Ab initio Accelerated MD

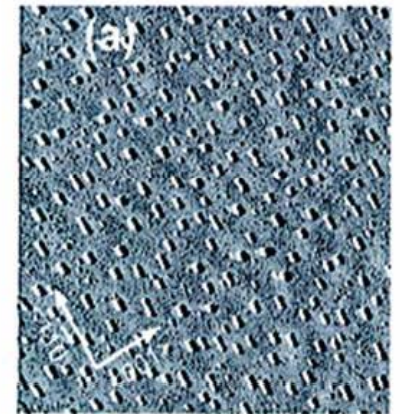
Modified VASP Code

Diffusion Pathways

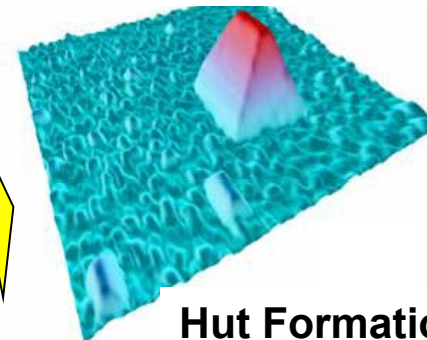
K. A. Fichthorn et al., *J. Phys. Cond. Matt.*  
**21**, 084212 (2009).



Atoms Hopping ( $\text{\AA}$ , ps)



Hut Organization ( $\mu\text{m}$ , min)



Hut Formation (nm, min)

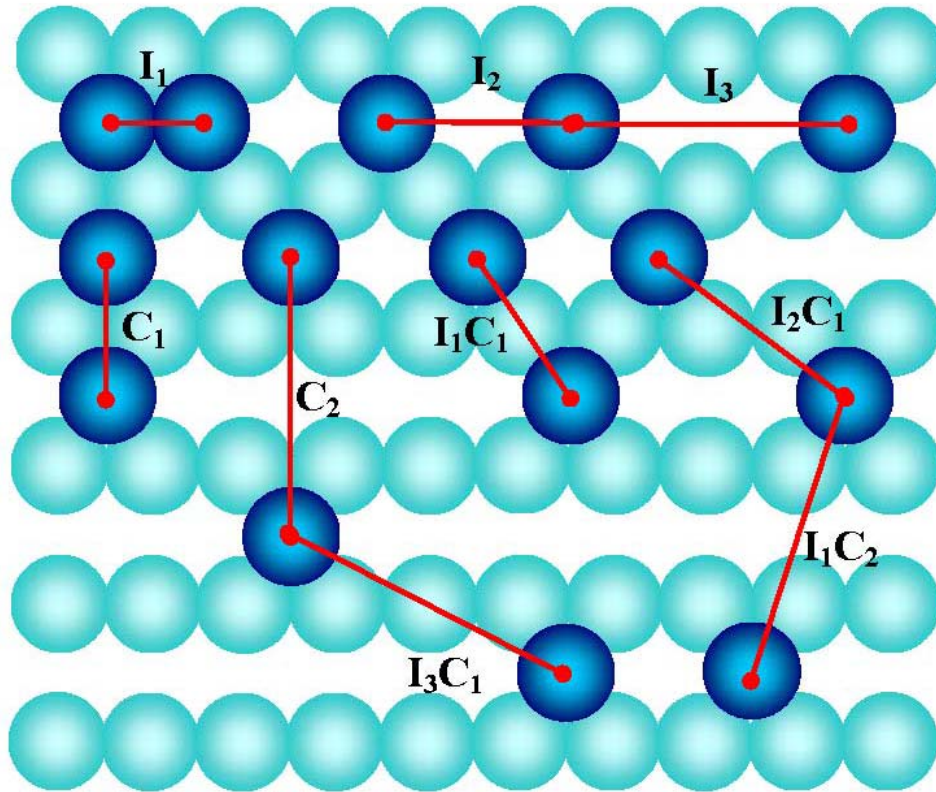
## Kinetic Monte Carlo Continuum

Growth Simulations

Y. Tiwary and K. Fichthorn (In preparation).

# Pair Interactions on Al(110)

## DFT GGA



$$E_{I_1} = -0.091 \text{ eV}$$

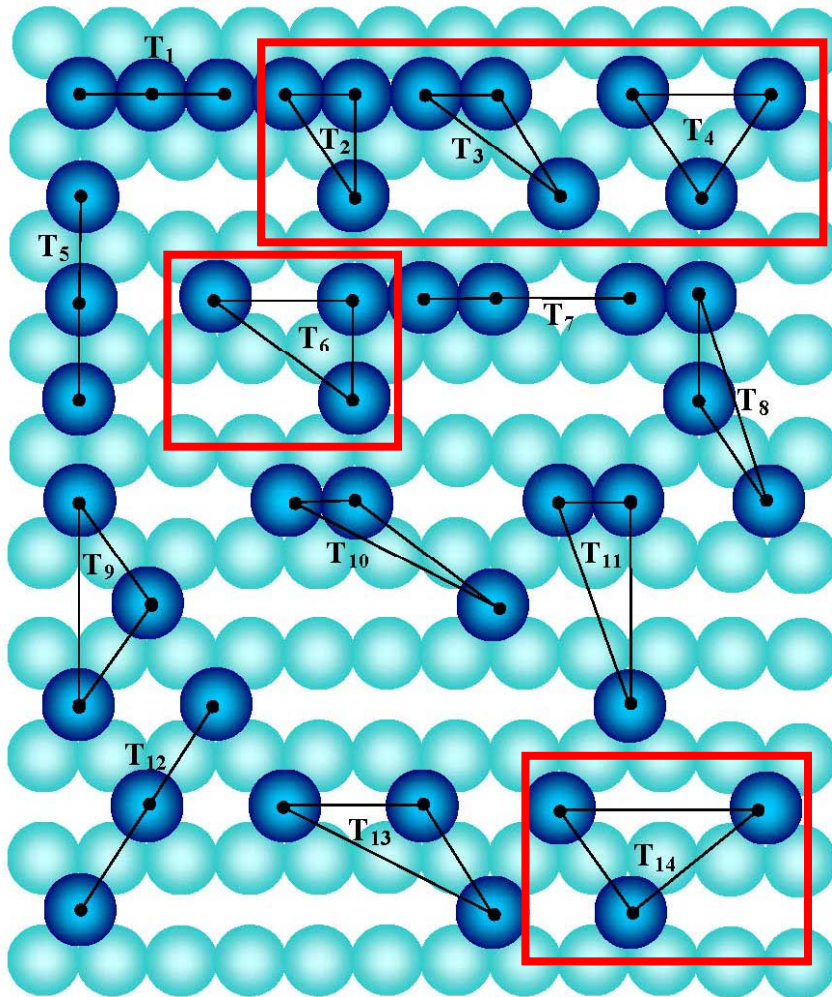
$$E_{C_1} = 0.049 \text{ eV}$$

All long-range  
pair interactions  
are repulsive!

Y. Tiwary and K. Fichtorn,  
*Phys. Rev. B* **75**, 235451 (2007)

How Can We  
Have Huts???

# Attractive Trios...

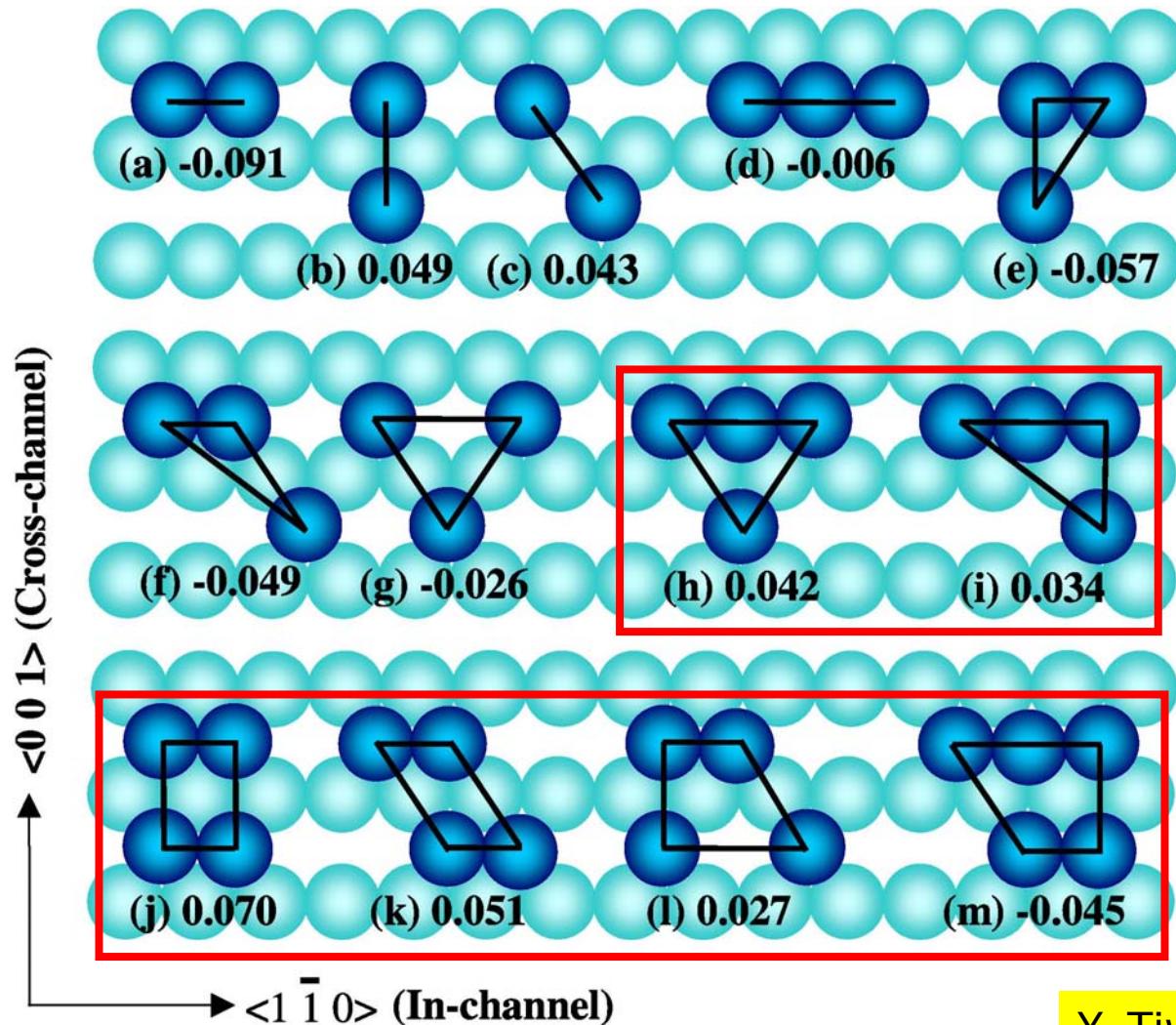


$T_1 = -0.006$ eV	$T_8 = 0.011$
$T_2 = -0.060$	$T_9 = 0.019$
$T_3 = -0.044$	$T_{10} = -0.005$
$T_4 = -0.021$	$T_{11} = 0.015$
$T_5 = 0.032$	$T_{12} = 0.004$
$T_6 = -0.019$	$T_{13} = 0.017$
$T_7 = -0.025$	$T_{14} = -0.017$

Trios Can Stabilize  
Cross-Channel  
Bonding, But...

Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **75**, 235451 (2007).

# High-Order Many-Body Interactions Are Significant!!



Many-Body (Elastic) Interactions Make the Lattice-Gas Approach Unwieldy...

Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **78**, 205818 (2008).

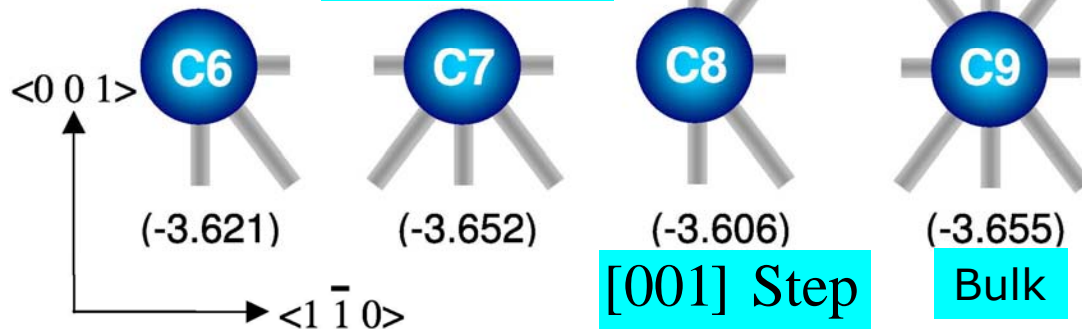
# The Connector Model

Combine groups of many-body interactions into structural units with a single interaction energy

Single Atom



$[1\bar{1}0]$  Step



$[001]$  Step

Bulk

Connectors Contain Key Energies in Thin-Film Growth e.g., Steps

$$\lambda_{[1\bar{1}0]} = C7 - C9 = 0.003 \text{ eV/atom}$$

$$\lambda_{[001]} = C8 - C9 = 0.048 \text{ eV/atom}$$

$$\lambda_{[001]} / \lambda_{[1\bar{1}0]} = 16$$

Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **78**, 205818 (2008).



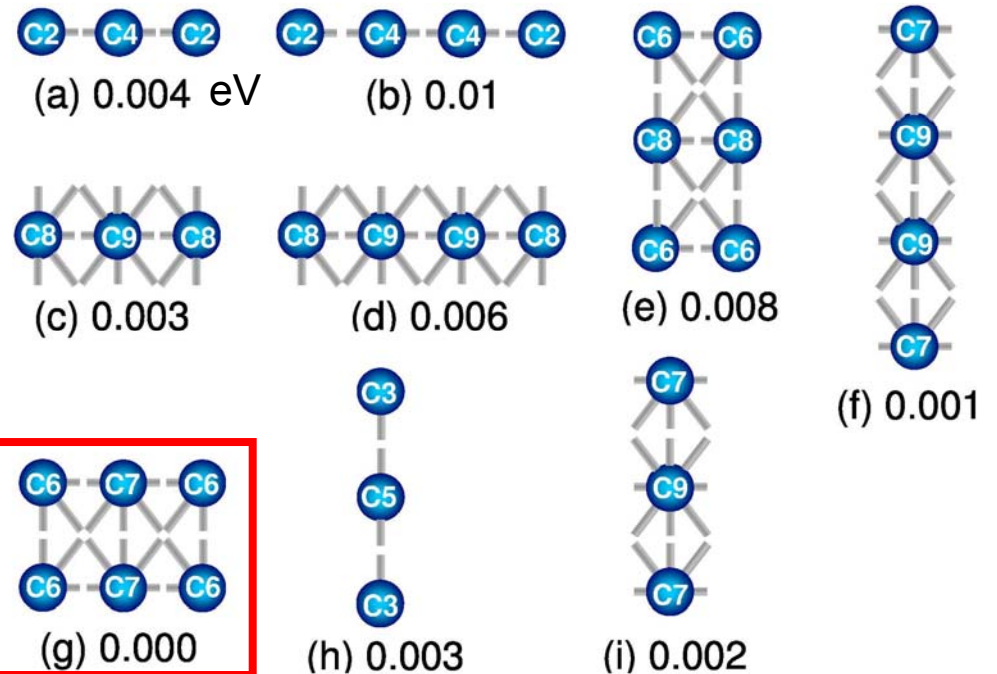
# The Connector Model is Accurate and Efficient

## Connector vs. DFT

Connector

$$E = 4C_6 + 2C_7$$

vs. Lattice Gas



$$E = \sum E_0 + \sum \text{pairs} + \sum \text{trios} + \sum \text{quartos} + \sum \text{pentas} + \sum \text{hexas}$$

$$6 + 15 + 10 + 15 + 6 + 1$$

Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **78**, 205818 (2008).

> 50 interactions

# Connector Model Compares Favorably To Fitted Cluster Expansion Model

$$CV = \sqrt{\frac{1}{M} \sum_{i=1}^M [E^{DFT}(i) - E^{CE}(i)]^2}$$

M Atom Configurations  
n terms in CE

A. van de Walle and G. Ceder, *J. Phase. Equilib.* **23**, 348 (2002).

G. L. W. Hart, V. Blum, M. J. Walorski, and A. Zunger, *Nature Mat.* **4**, 391 (2005).

N. A. Zarkevich and D. D. Johnson, *Phys. Rev. Lett.* **92**, 255702 (2004).

R. Drautz and A. Díaz-Ortiz, *Phys. Rev. B* **73**, 224207 (2006).

Y. Tiwary and K. Fichthorn,  
*Phys. Rev. B* **78**, 205818 (2008).

	Interaction Energy (eV)						Connector
	FLG	n=18	n=14	n=10	n=6	n=4	
N1	-0.091	-0.086	-0.092	-0.096	-0.093	-0.094	.
N2	0.060	0.060	0.062	0.063	0.063	0.062	.
N3	0.043	0.047	0.046	0.044	0.026	.	.
N4	0.045	0.045	0.040	0.045	0.039	0.041	.
N5	0.036	0.009	.	.	.	.	.
N6	0.010	0.010	0.010	0.009	0.011	.	.
T1	-0.006	-0.016	.	.	.	.	.
T2	-0.067	-0.067	-0.062	-0.062	-0.033	-0.021	.
T3	-0.049	-0.030	-0.016	-0.008	.	.	.
T4	-0.026	-0.038	-0.030	-0.032	.	.	.
T5	0.005	0.003	0.000	.	.	.	.
T6	-0.026	0.002	0.014	.	.	.	.
Q1	0.071	0.093	0.081	0.062	.	.	.
Q2	0.042	0.067	0.060	0.039	.	.	.
Q3	0.061	0.044	0.023	.	.	.	.
Q4	0.034	0.023	.	.	.	.	.
Q5	0.027	0.022	.	.	.	.	.
F1	-0.045	-0.058	-0.023	.	.	.	.
CV	0.014	0.021	0.009	0.009	0.013	0.020	0.007
e(eV/atom)	0.030	0.014	0.018	0.018	0.018	0.022	0.006

# Are Huts Thermodynamically Stable?

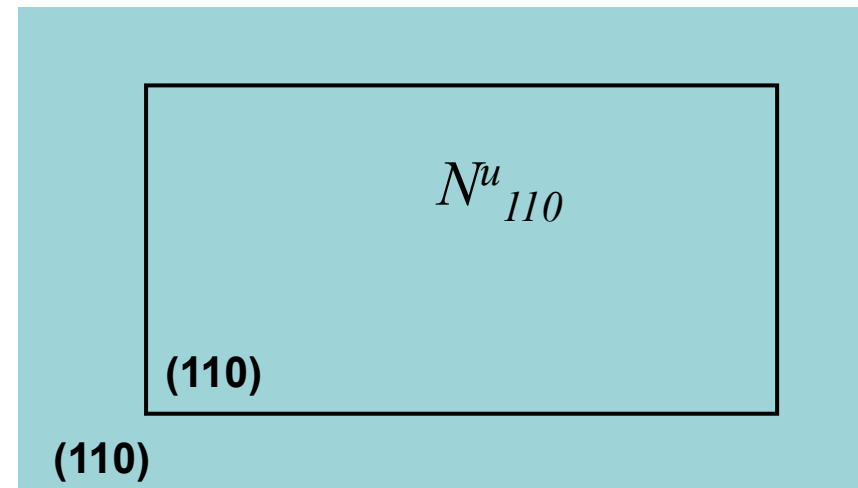
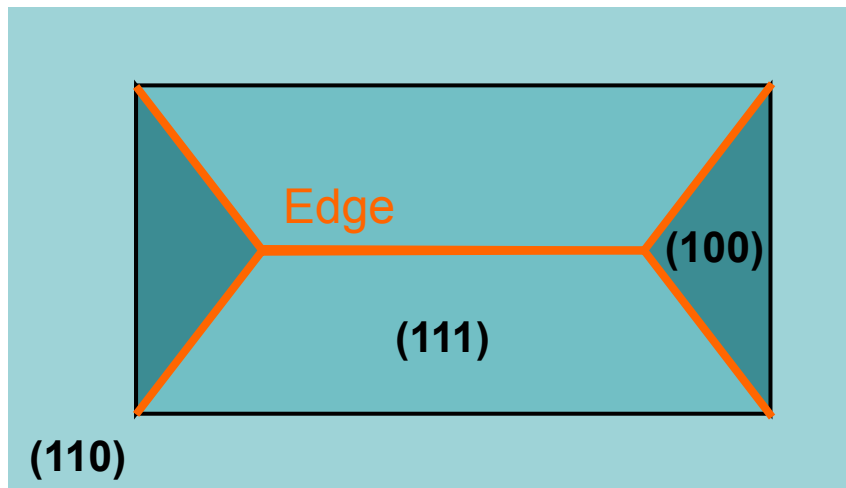
## Hut Formation Energy

$\gamma$  = Surface Energy (eV/atom)

$N$  = # atoms

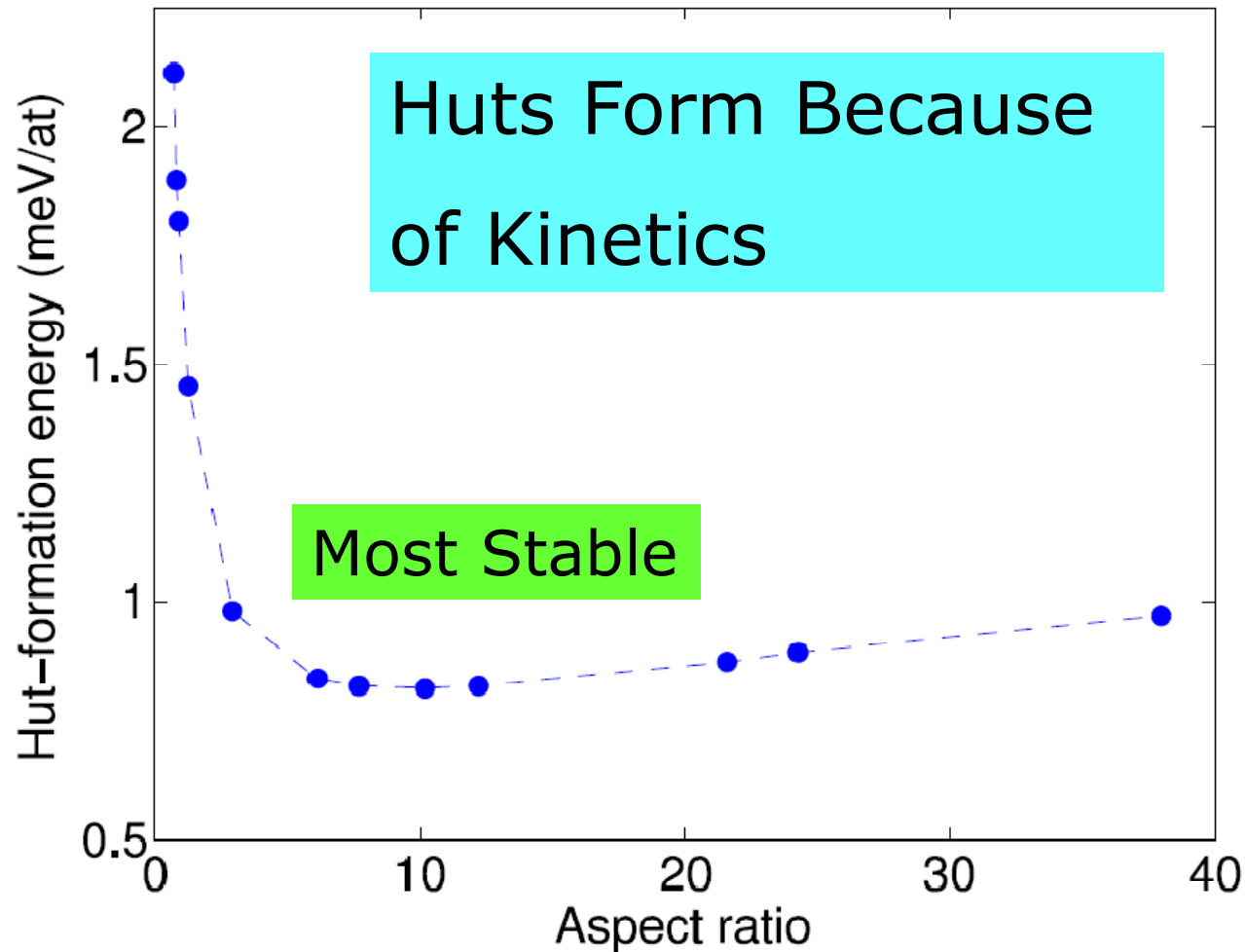
$$\begin{aligned}\Delta E_{hut} &= E_{substrate+hut} - E_{substrate+ML} \\ &= \left( N_{111}^f \gamma_{111} + N_{100}^f \gamma_{100} + N_{edge}^f \gamma_{110} \right) - N_{110}^u \gamma_{110}\end{aligned}$$

$$\gamma_{110} = 0.665 \text{ eV/atom}, \gamma_{100} = 0.454 \text{ eV/atom}, \gamma_{111} = 0.342 \text{ eV/atom}$$



If  $\Delta E_{hut} < 0$ , Hut Favored Over Layer

# Huts Are Not Energetically Favored



Consistent with Experiment....

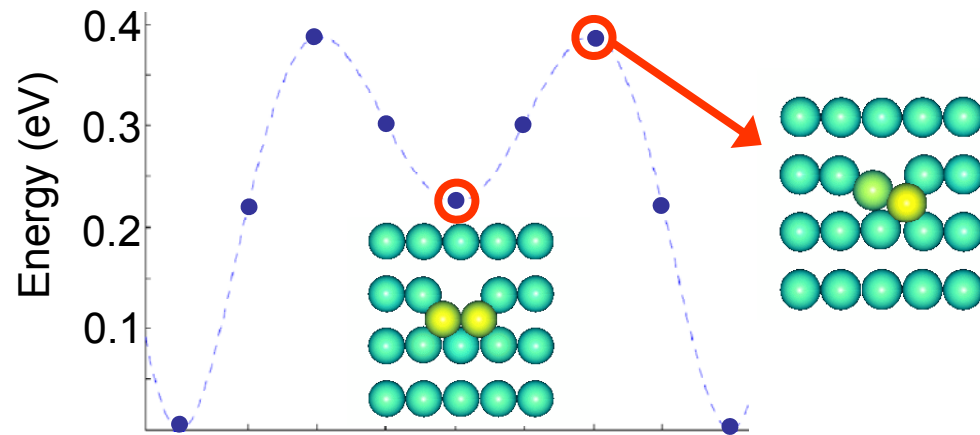
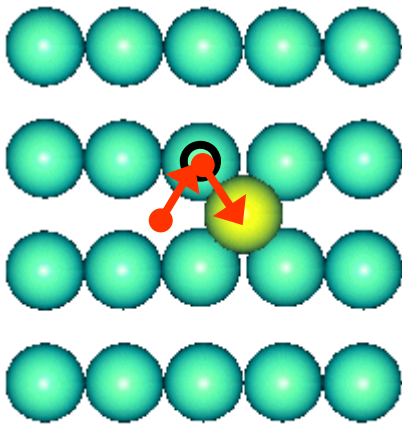
Bautier de Mongeot *et al.*, *Phys. Rev. Lett.* **91**, 016102 (2003).

# Al Diffusion on Al(110)

## Climbing-Image Nudged-Elastic Band Method

G. Henkelman, B. Uberuaga, and H. Jonsson, *J. Chem. Phys.* 113, 9901 (2000)

### In-Channel



Local Minima in the Diffusion Pathway

$\Delta E$  = 0.40 eV  
Stumpf: 0.33 eV  
Zhu: 0.33 eV

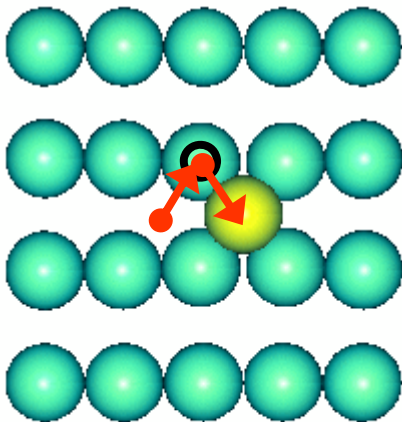
R. Stumpf and M. Scheffler, *Phys. Rev. B* **53**, 4958 (1996).  
W. Zhu et al., *Phys. Rev. Lett.* **92**, 106102 (2004).  
Y. Tiwary and K. Fichthorn, *Phys. Rev. B* **81** 195421 (2010)

# Al Diffusion on Al(110)

## Climbing-Image Nudged-Elastic Band Method

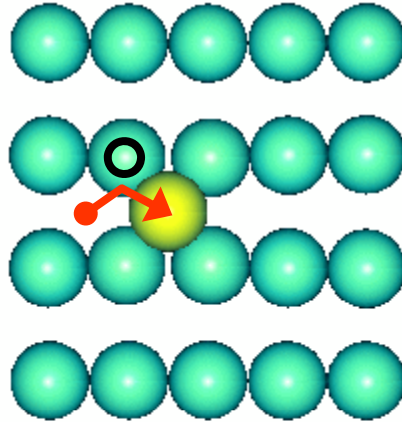
G. Henkelman, B. Uberuaga, and H. Jonsson, *J. Chem. Phys.* 113, 9901 (2000)

### In-Channel



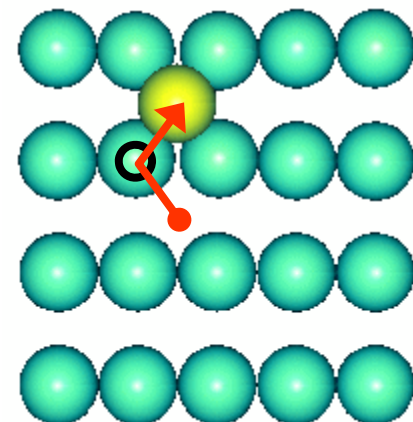
$\Delta E = 0.40$  eV  
Stumpf: 0.33 eV  
Zhu: 0.33 eV

### In-Channel



$\Delta E = 0.38$  eV

### Cross-Channel



$\Delta E = 0.38$  eV  
Stumpf: 0.62 eV  
Zhu: 0.49 eV

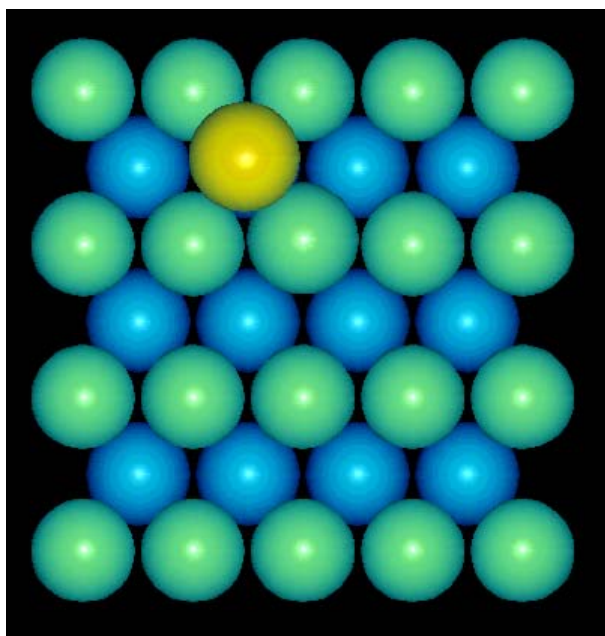
## Isotropic Diffusion...

R. Stumpf and M. Scheffler, *Phys. Rev. B* **53**, 4958 (1996).

W. Zhu et al., *Phys. Rev. Lett.* **92**, 106102 (2004).

Y. Tiwary and K. Fichthorn, *Phys. Rev. B* **81** 195421 (2010)

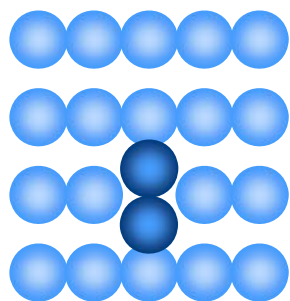
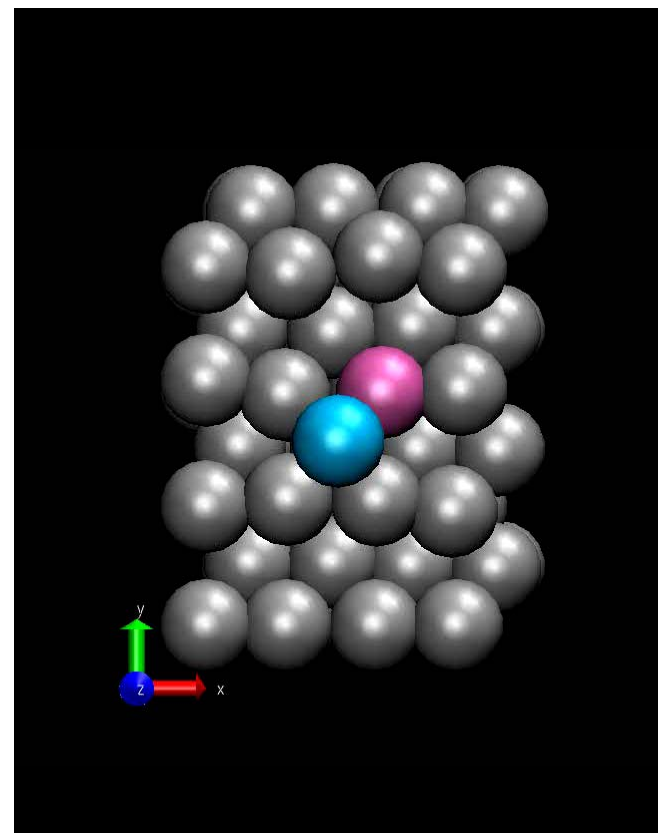
# Accelerated Ab Initio MD



Climbing-Image  
Nudged Elastic  
Band Method

VS.

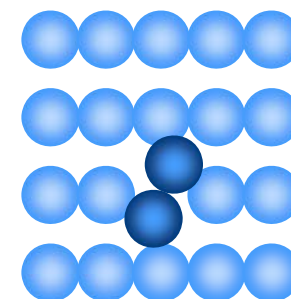
Accelerated  
AIMD



$$E_B = 0.38 \text{ eV}$$

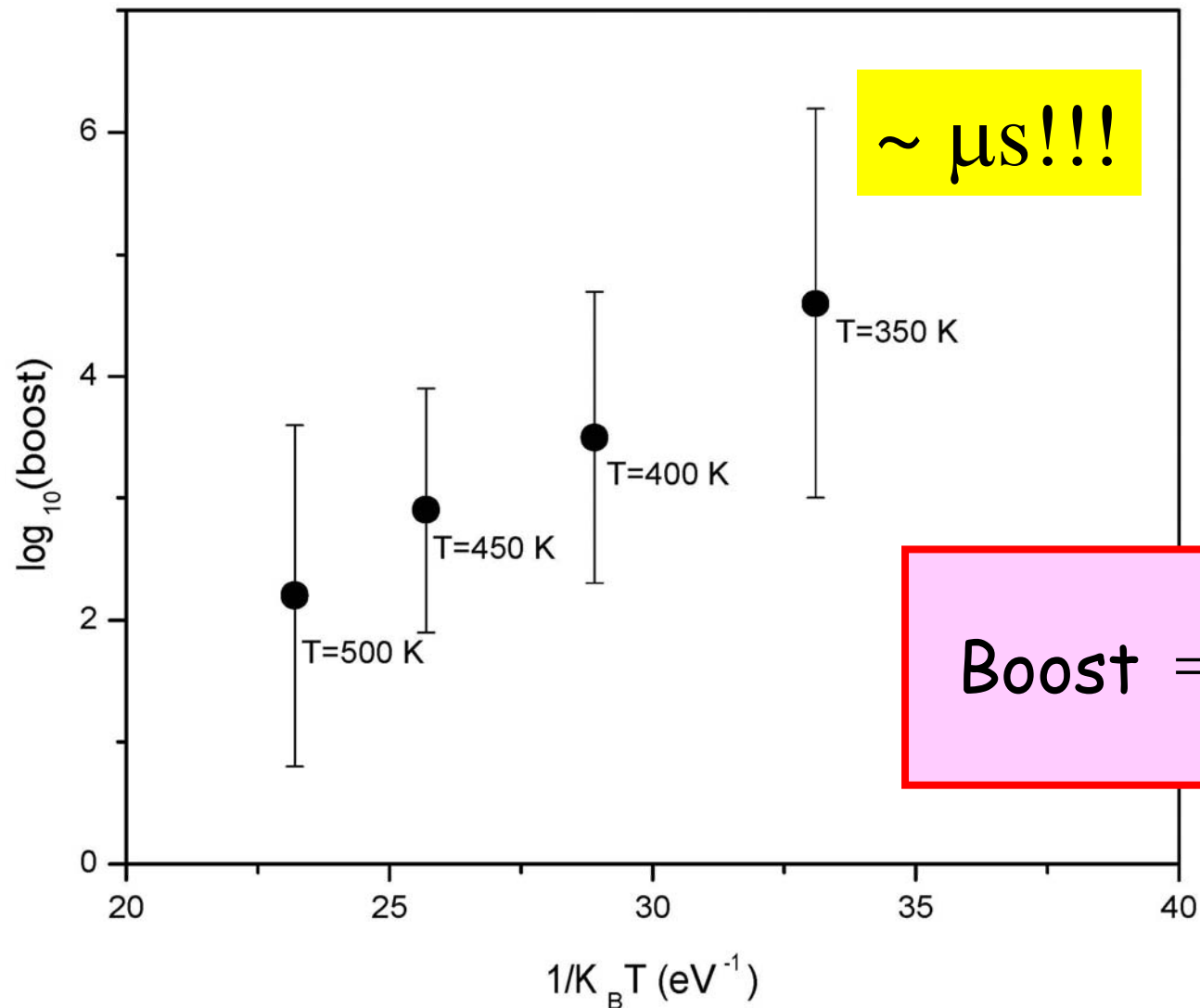
Cross-Channel  
Diffusion Is Faster!

K. Fichthorn et al.,  
*J. Phys. Cond. Matt.*  
**21**, 084212 (2009).



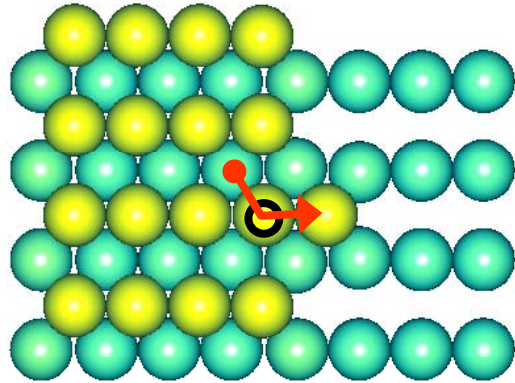
$$E_B = 0.33 \text{ eV}$$

# The Boost in *ab initio* MD



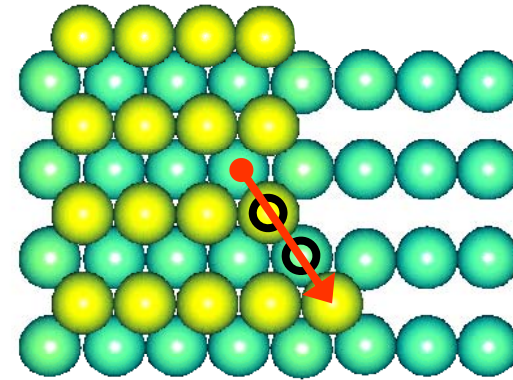


# Diffusion Up and Down Steps: Diagonal Dominance

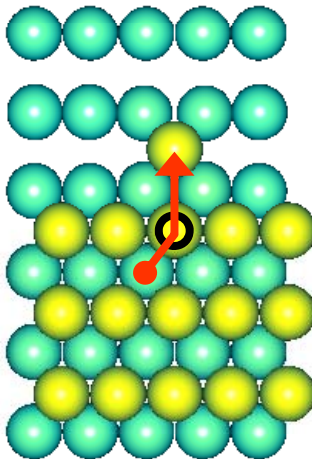


(100) Step

Up (Down): 0.58 (0.44)  
Zhu : 0.60 (0.43)

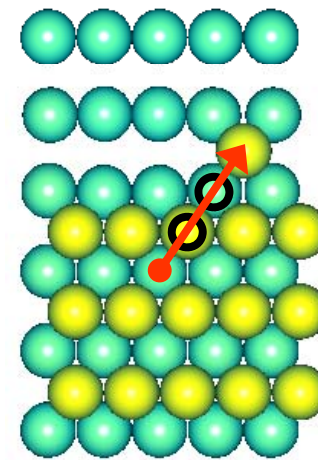


**Up (Down): 0.49 (0.36)**



(111) Step

Up (Down): 0.65 (0.68)  
Zhu : 0.67 (0.71)



**Up (Down): 0.58 (0.62)**

Zhu et al., PRL **92** 106102 (2004)

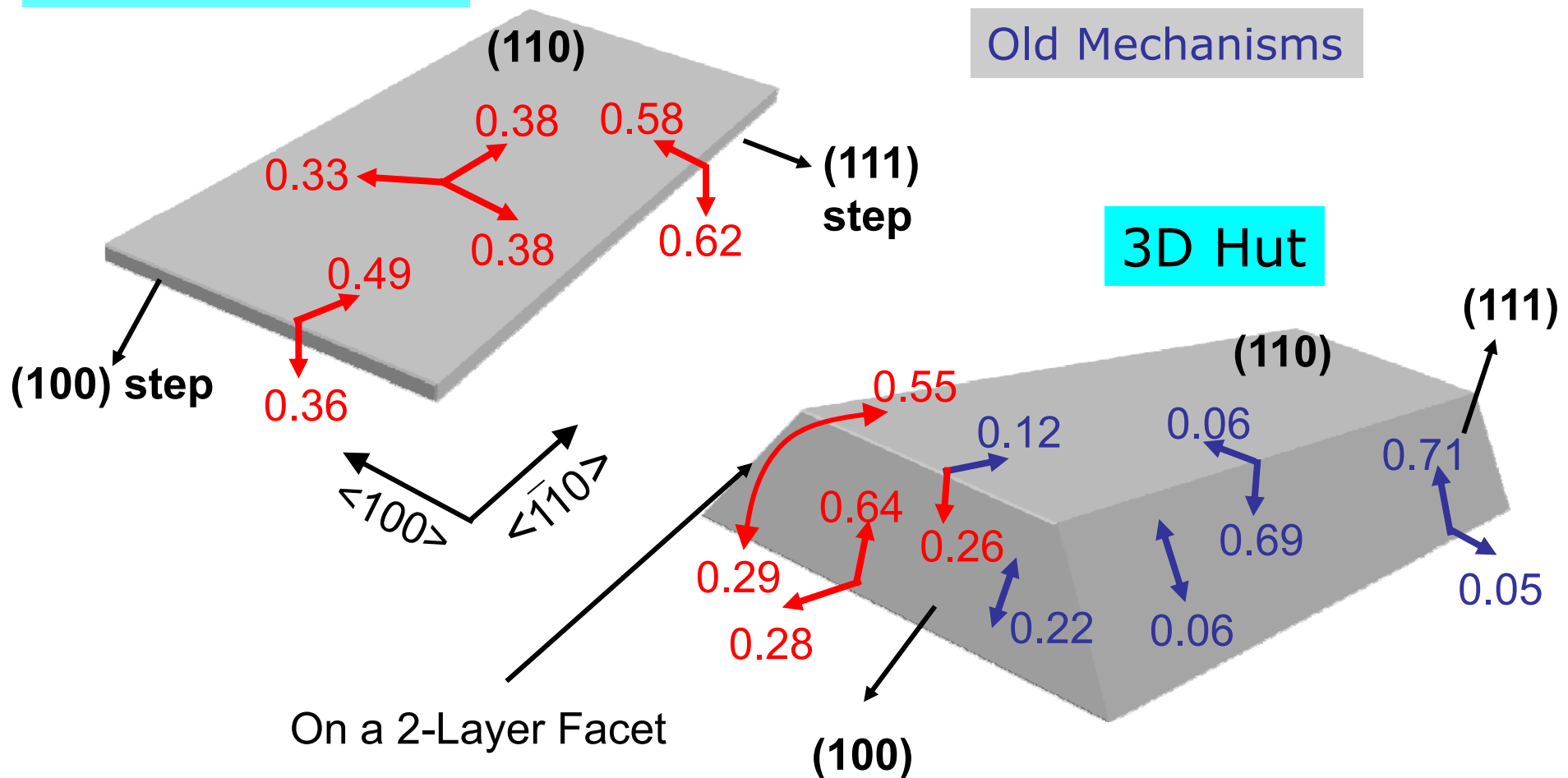
Y. Tiwary and K. Fichthorn PRB **81**, 195421 (2010).

# Barriers for Single-Atom Hops (eV)

Mono-Atomic  
High Island

New Mechanisms

Old Mechanisms

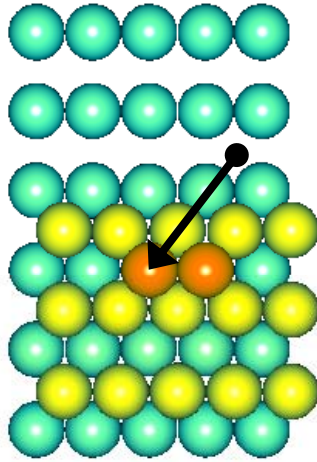


Y. Tiwary and K. Fichthorn, Phys. Rev. B **81**, 195421 (2010).

# Co-operation Between Atoms



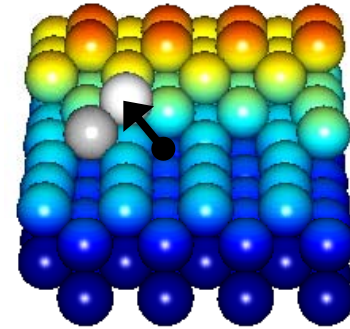
Atoms Pull  
Others Up



0.50 vs. 0.58 eV (isolated)



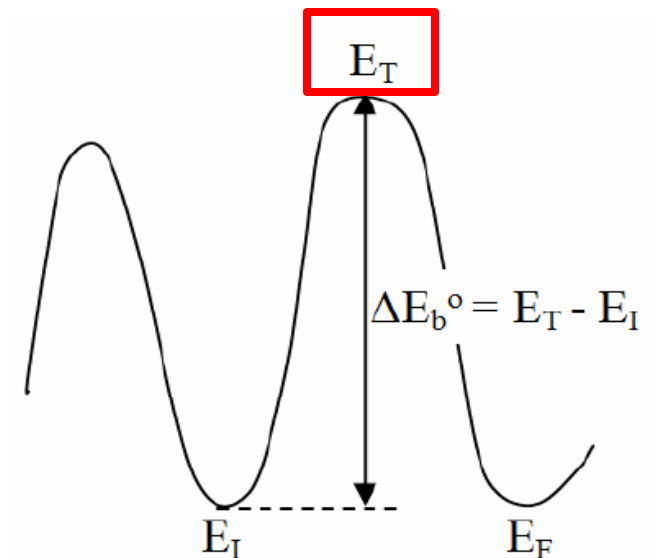
Atoms Push  
Others Up



0.47 vs. 0.67 eV (isolated)

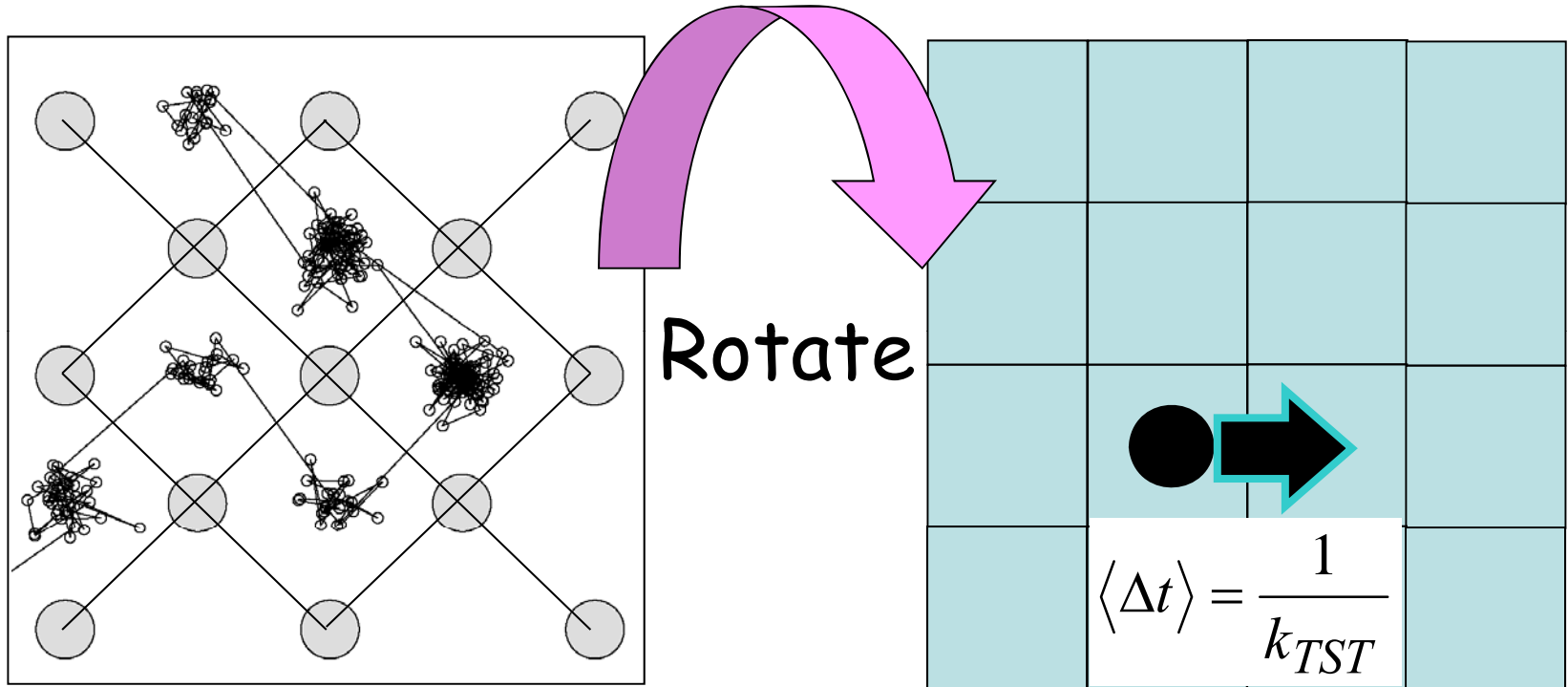
Transition-State  
Interactions are Important!

Y. Tiwary and K. Fichthorn , Phys. Rev. B **81**,  
195421 (2010).



# Kinetic Monte Carlo: Coarse-Graining MD

K. A. Fichthorn and W. H. Weinberg, J. Chem. Phys. 95, 1090 (1991).



MD of Co on Cu(001):  
The Whole Trajectory

kMC: Coarse-Grained Hops

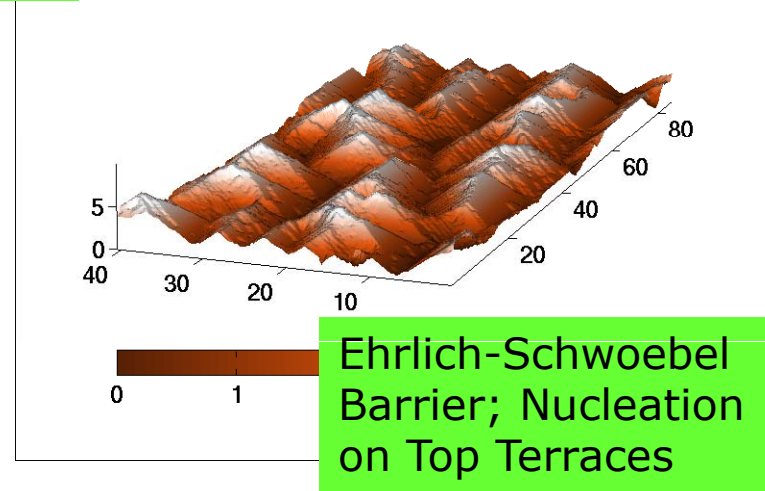
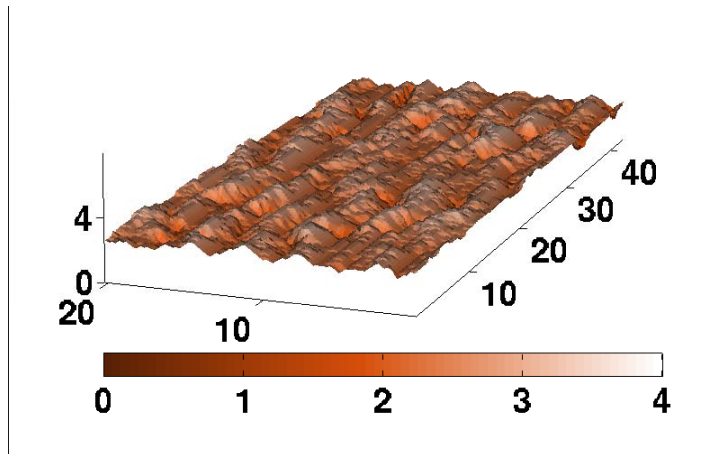
Rare Events: 
$$k_{TST} = \left\langle \frac{v}{2} \right\rangle \frac{\int \delta(\mathbf{R} - \mathbf{R}^\ddagger) \exp(-V(\mathbf{R})/k_B T)}{\int \exp(-V(\mathbf{R})/k_B T)}$$

# KMC Simulations of Al(110) Homoepitaxy

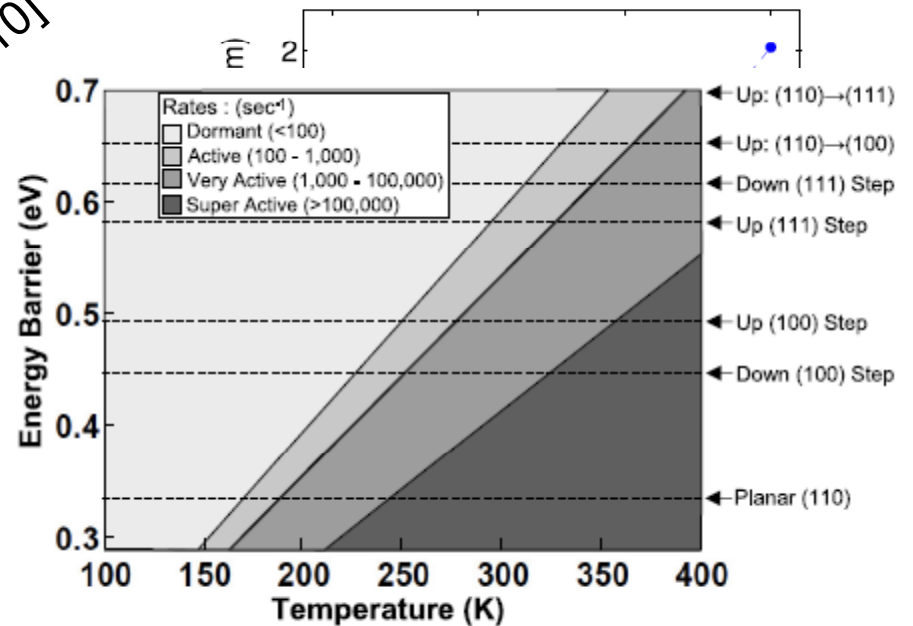
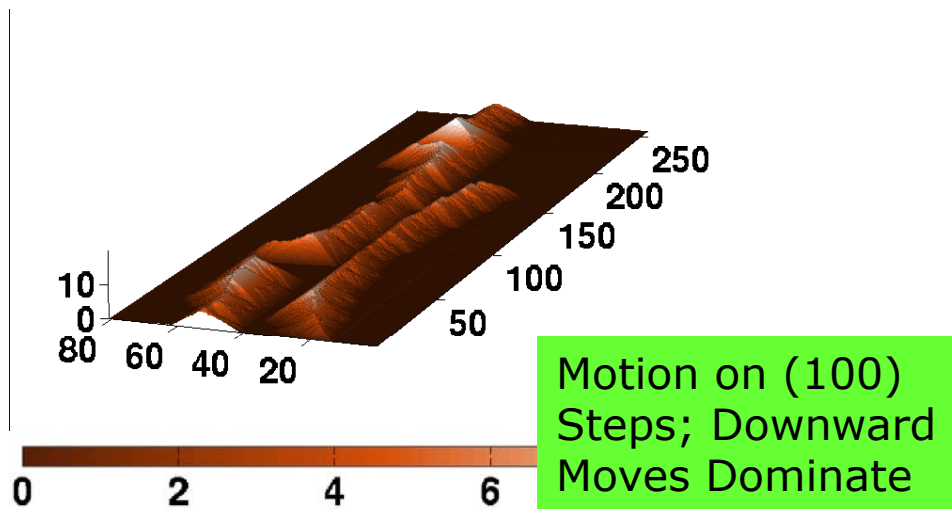
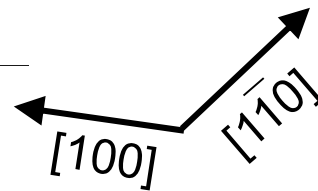
T=150 K;  $\theta=20$  ML

Dimensions in nm

T=200 K;  $\theta=20$  ML

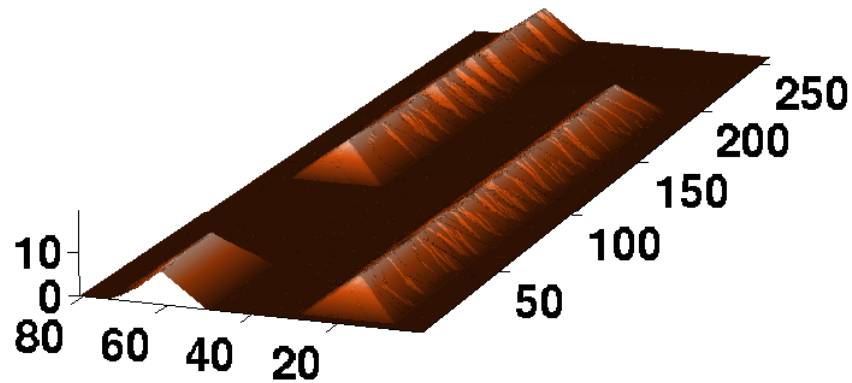


T=250 K;  $\theta=10$  ML



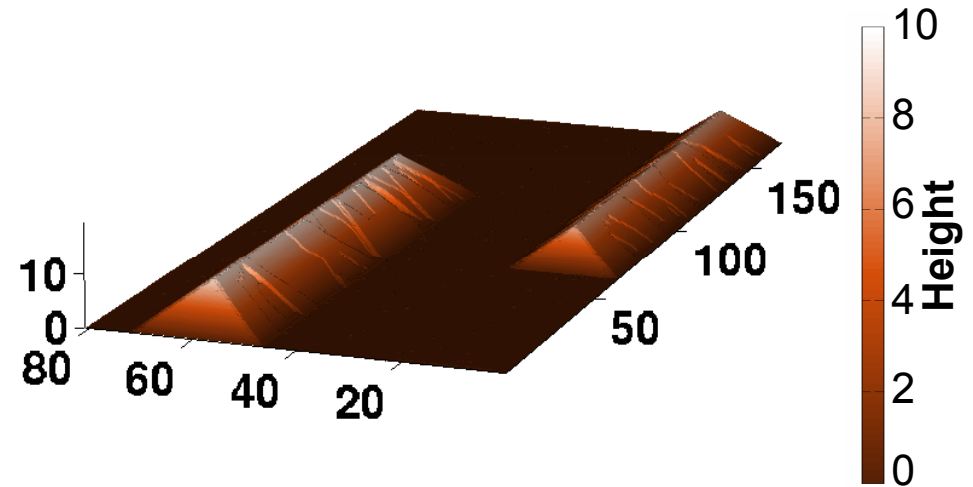
# KMC Simulations: Rising Huts

$T=350$  K,  $\theta=10$  ML  
( $F=150$  ML/min,  $\theta=0.25$  ML)



Aspect Ratio  $\approx 8:1$

$T=400$  K,  $\theta=10$  ML  
( $F=350$  ML/min,  $\theta=0.25$  ML)

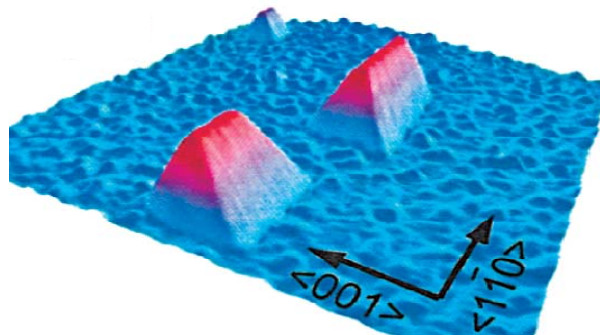


Aspect Ratio  $\approx 5:1$

Experiment (AFM)

Bautier de Mongeot *et al.*, *Phys. Rev. Lett.* **91**, 016102 (2003).

Zhu *et al.*, *Phys. Rev. Lett.* **92**, 106102 (2004).



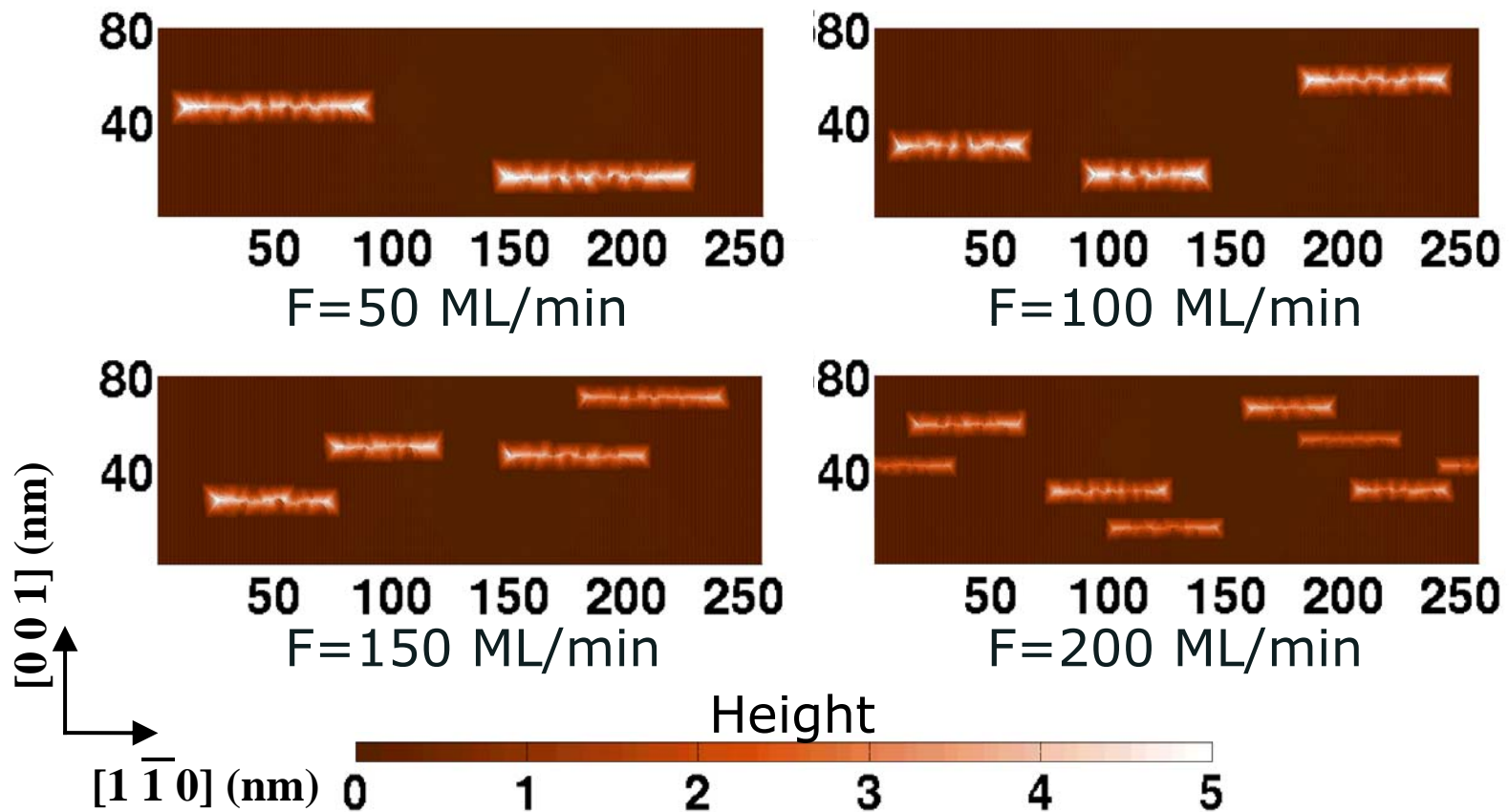
All dimensions in nm

$T=450$  K,  $F=1$  ML/min,  
 $\theta=10$  ML

Aspect Ratio  $\approx 3:1$

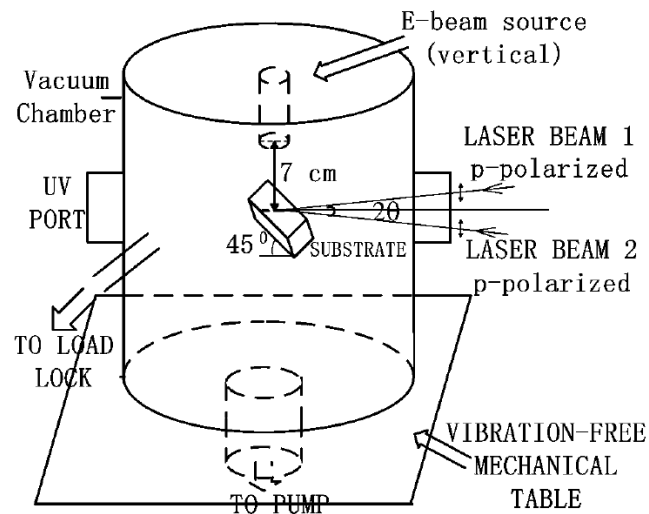
# KMC: Controlling Hut Density via Flux

( $T=325$  K,  $\theta=2$  ML)

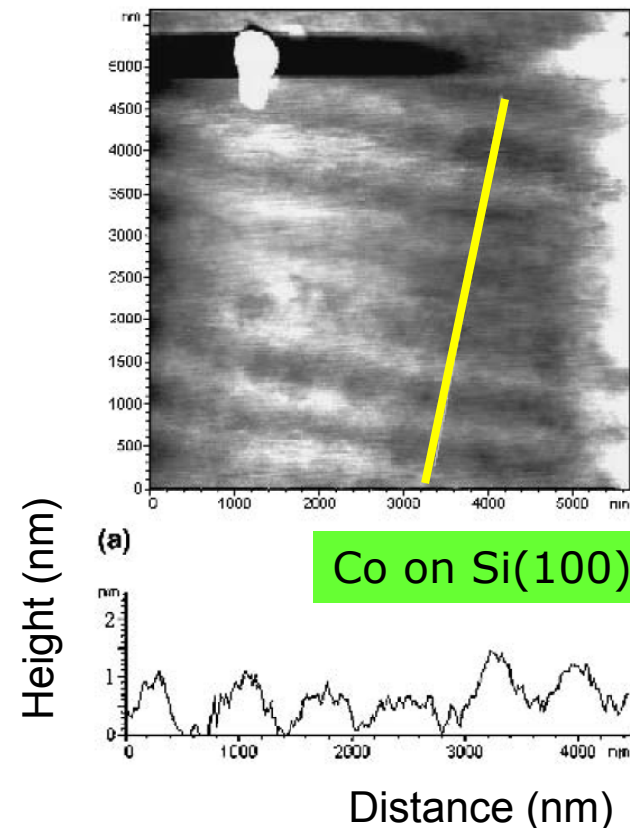
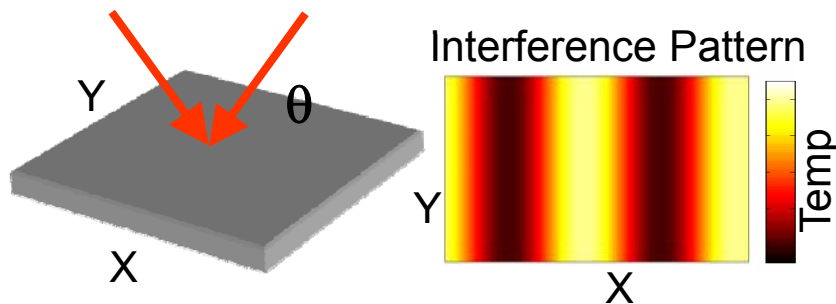


Now All We Need is Good Hut Placement

# Hut Positioning: Pulsed Dual-Beam Laser Interference



Zhang & Kalyanaraman, J. Mater. Res. **19**, 595 (2004)



## Laser Interference Parameters:

### Temperature:

Energy Density of Laser  
(5 mJ/cm<sup>2</sup> = 50 K)

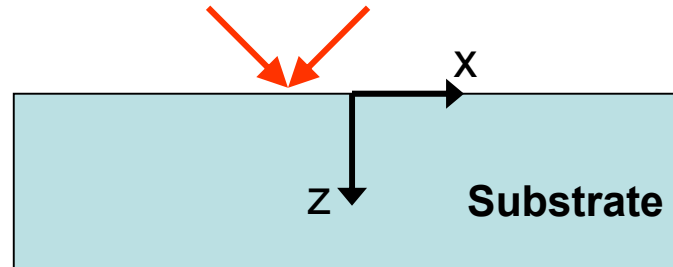
### Fringe Width or Wavelength (532 nm):

Wavelength of Laser (266 nm)  
Interference Angle (29°)



# Temperature Profile: Pulsed Two-Beam Interference

$$\rho c_p \frac{\partial T}{\partial t} = k \left( \frac{\partial^2 T}{\partial x^2} + \frac{\partial^2 T}{\partial z^2} \right) + q$$



$T(x, z, t)$ : Temperature,  $\rho$ : Density,  $c_p$ : Specific heat,  
 $k$ : Thermal conductivity

## Power Generation

$$q = \alpha \frac{E(x)}{\sigma \sqrt{2\pi}} \exp\left(-\frac{(t - t_p)^2}{2\sigma^2}\right) (1 - R) \exp(-z\alpha)$$

$t_p$ : Pulse width of laser beam,  $\alpha$ : Absorption coefficient,  $R$ : reflectivity

## Interference Intensity

$$E(x) = 2E_o \left[ \cos\left(\frac{2\pi x}{\Lambda}\right) + 1 \right]$$

$E_o$ : Energy density of incident laser beam

## Fringe Width

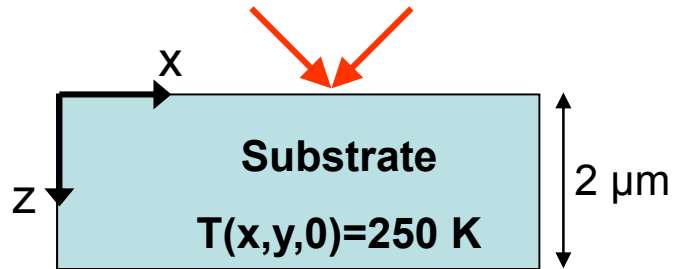
$$\Lambda = \lambda / [2 \sin(\theta)]$$

$\lambda$ : wavelength of laser

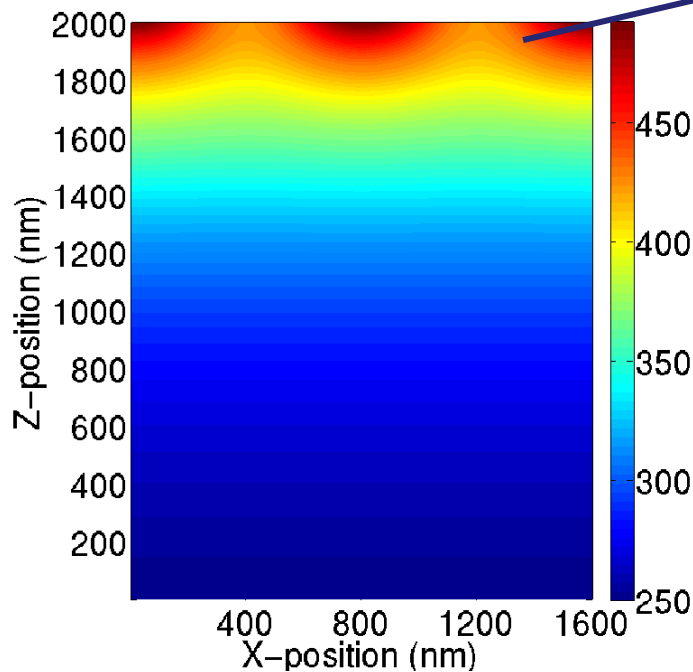
$\theta$ : Interference angle

Lasagni *et al.*, Appl. Surf. Sci. 247, 32 (2005)

# Temperature Profile



$E=0.4\ \text{J}/\text{cm}^2$ ,  $\Lambda=800\ \text{nm}$   
(Nanohut spacing at  $450\ \text{K}$ )

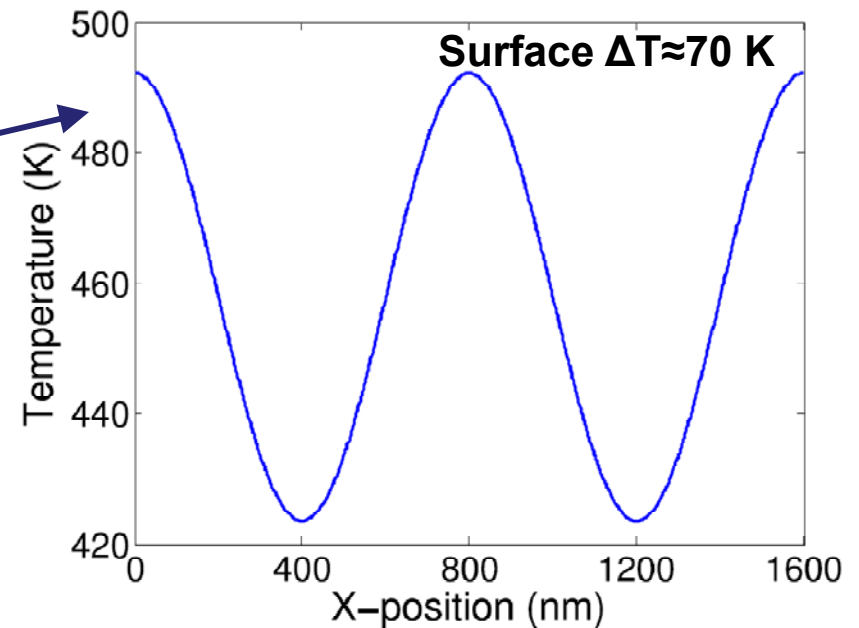


Temperature (K)

$\lambda=266\ \text{nm}$ ,  $t=\text{Pulse Width } (t_p=9\ \text{ns})$

**Optical Properties of Aluminum:**

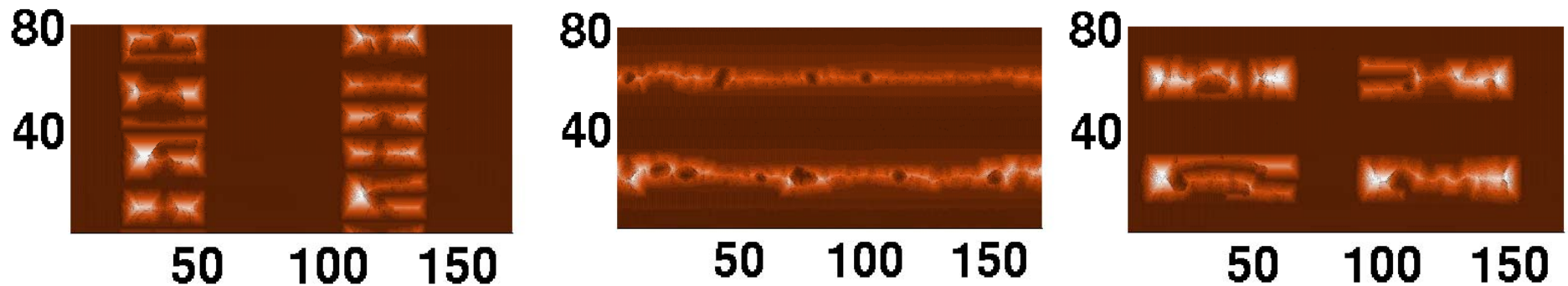
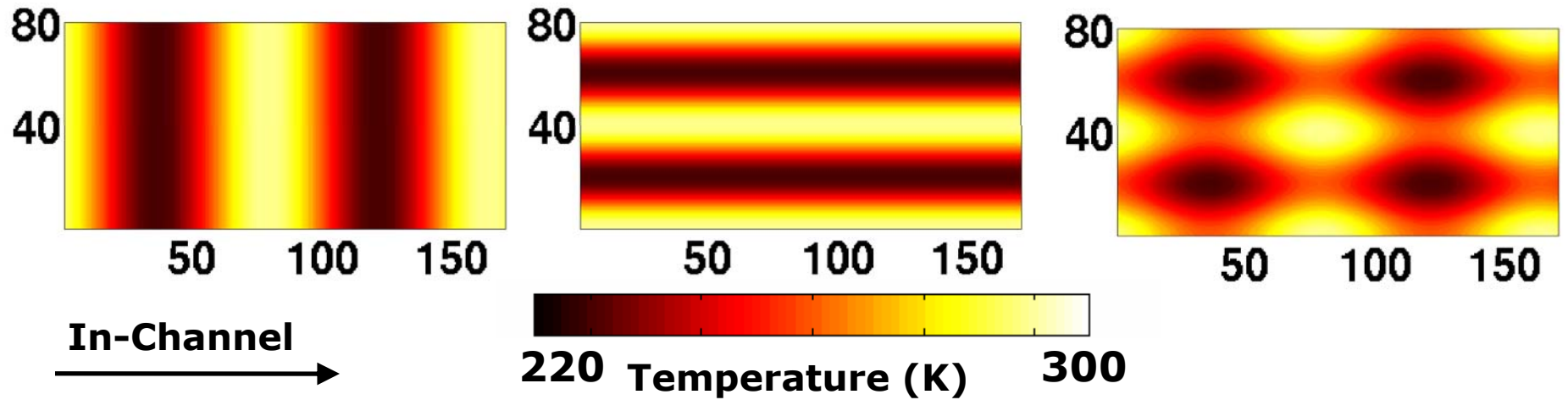
Weaver *et al.*, Physics Data, Optical Properties of Metals, Vol. 18 (1981)



**Significant temperature gradients for relevant spacings!**

# KMC Simulation of Hut Placement

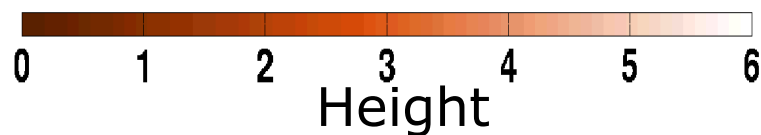
Dual/Four-Beam Laser Interference ,  $F=1$  ML/min,  $\theta=5$  ML



Nano-Ripples

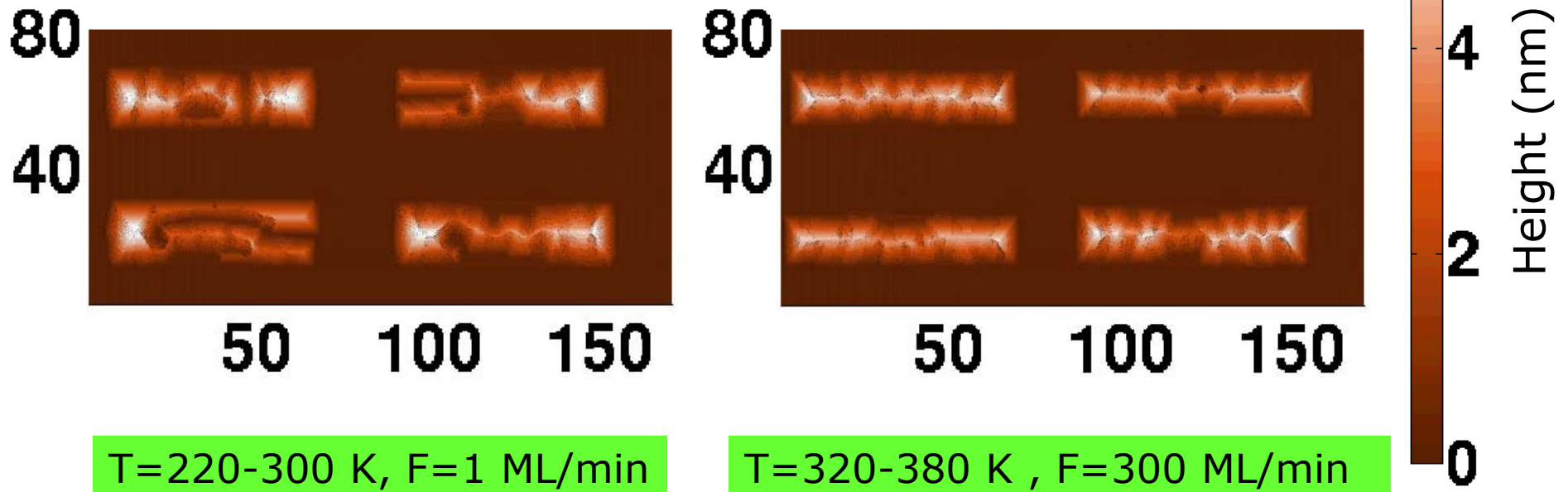
Array of Mounds

Dimensions in nm



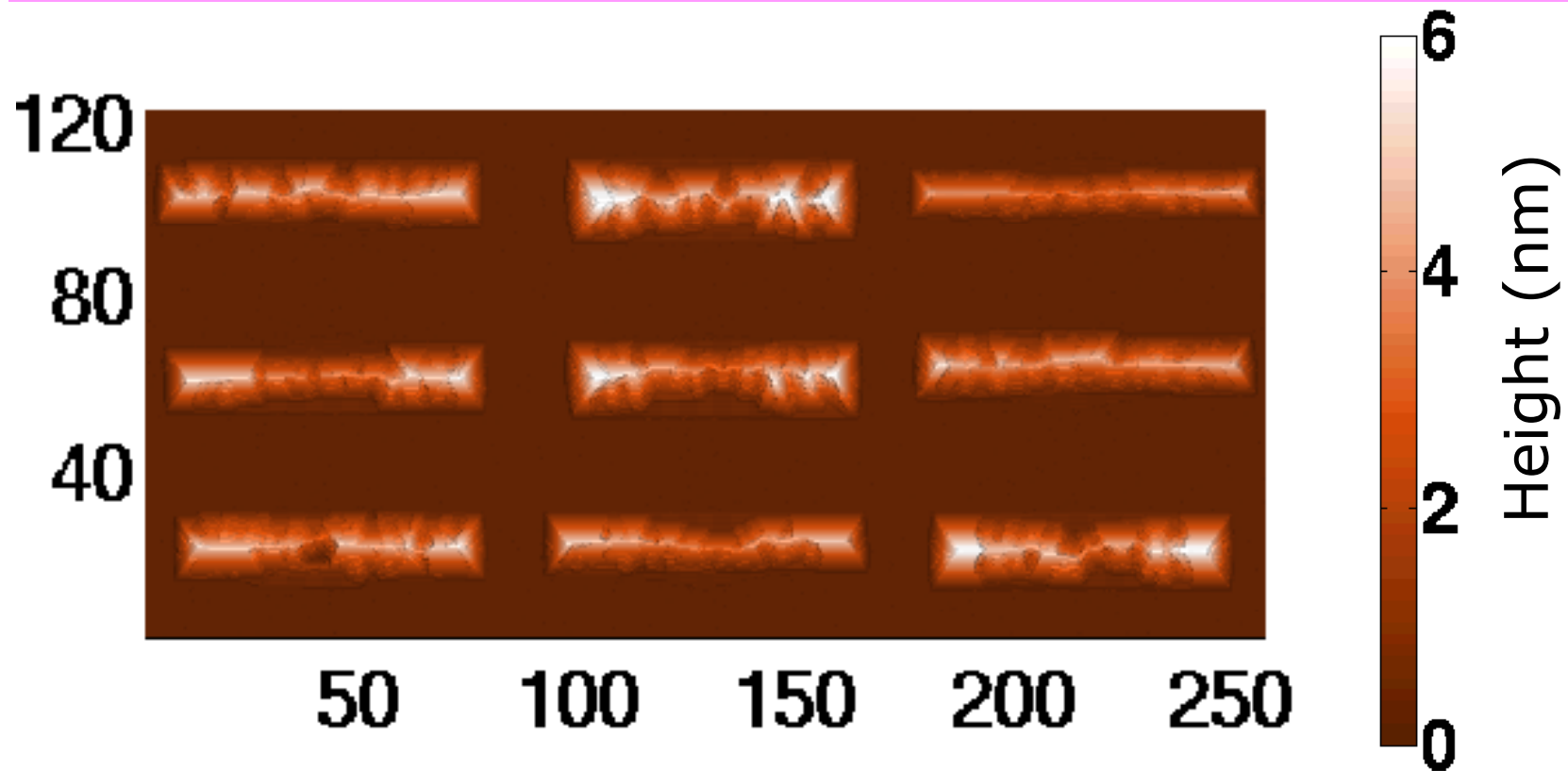
# KMC Simulation of Hut Placement

Four-Beam Laser Interference,  $\theta=5$  ML



Tune Hut Morphology by Adjusting Temperature

# KMC: Four-Beam Laser Interference



$T=300-360$  K,  $F=200$  ML/min,  $\theta=5$  ML

# Conclusions

- Al(110) [and possibly other fcc(110)] Homoepitaxy is Interesting:  
Increased Roughening with Increasing Temperature: HUTS
- Many-Body Interactions and Diffusion are Key
  - Connector Model
  - Ab initio Accelerated Molecular Dynamics
- Hut Placement by Pulsed Dual- or Four-Beam Laser Interference